

L Number	Hits	Search Text	DB	Time stamp
8	3	histogram same equal\$9 same gain same offset same (image or pixel)	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 15:03
1	1	histogram with equal\$9 with gain with offset	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 15:04
15	3	histogram near2 equal\$9 same gain with offset	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 15:05
22	22	histogram near2 equal\$9 and image and pixel and gain with offset	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 15:05

L Number	Hits	Search Text	DB	Time stamp
1	2066	(("382/141-151") or ("348/87,126")).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 14:09
15	1	electron adj beam with (benefit or advantag\$2) and (((("382/141-151") or ("348/87,126")).CCLS.)		2001/10/03 14:11
8	117	electron adj beam and (((("382/141-151") or ("348/87,126")).CCLS.)		2001/10/03 14:12

L Number	Hits	Search Text	DB	Time stamp
1	3595	wafer near2 inspect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 13:19
8	16	confocal with (stage or chuck or table) near (move\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 13:21

L Number	Hits	Search Text	DB	Time stamp
1	1294	silicon adj dioxide with transparent	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 12:38
8	2	(silicon adj dioxide with transparent) same wafer same inspect\$4	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 12:38
15	4	inspect\$4 near2 wafer and (silicon adj dioxide with transparent)	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 12:40
22	1216	transparent near2 (resist or photoresist)	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 12:40
29	20	inspect\$4 near2 wafer and (transparent near2 (resist or photoresist))	USPAT; US-PPGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/03 12:40